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OMB No. 0651-0011

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INFORMATION DISCLOSURE STATEMENT	Atty. Docket No.: 150.01150103	Serial No.: 10/771,043
	Applicant(s): Gurtej S. Sandhu	Confirmation No.: Unassigned
	Application Filing Date: February 3, 2004	Group: Unassigned
	Information Disclosure Statement mailed:	April 29, 2004

U.S. PATENT DOCUMENTS

Examiner Initial	Copy Enclosed	Document Number	Date	Name	Class	Subclass	Filing Date if Appropriate
46		3,585,073	06/15/71	Veenstra et al.			
		3,890,703	06/75	Frazee et al.			
		4,433,320	02/21/84	Murata et al.			
		4,442,422	04/10/84	Murata et al.			
		4,677,416	06/30/87	Nishimoto et al.			
		4,911,892	03/27/90	Grace et al.			
		5,147,737	09/15/92	Post et al.			
		5,331,287	07/19/94	Yamagishi et al.			
		5,337,018	08/09/94	Yamagishi			
		5,756,879	05/26/98	Yamagishi et al.			
		5,857,250	01/12/99	Riley et al.			
		5,906,726	05/25/99	Schneider et al.			
		6,280,604	08/28/01	Allen et al.			
		6,436,246	08/20/02	Sandhu			
		6,479,297	11/12/02	Sandhu			
		6,689,321	02/10/04	Sandhu			
		US 2003/0138958	07/24/03	Blalock			

FOREIGN PATENT DOCUMENTS

Examiner Initial	Copy Enclosed	Document Number	Date	Country	Class	Subclass	Translation
		1,151,482	05/07/69	Great Britain			Yr No
		1,576,658	08/01/69	France (w/abstract)			X

EXAMINER Jelen Yeh	Date Considered 05/26/03
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PAGE 4/7 * RCVD AT 4/29/2004 4:10:51 PM [Eastern Daylight Time] * SVR:USPTO-EFXXF-1/0 * DNIS:8729306 * CSID:1 612 305 1228 * DURATION (mm:ss):03:16

PAGE 7/9 * RCVD AT 12/9/2004 1:50:37 PM [Eastern Standard Time] * SVR:USPTO-EFXXF-1/0 * DNIS:8729306 * CSID:6123051228 * DURATION (mm:ss):02:50

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INFORMATION DISCLOSURE STATEMENT	Atty. Docket No.: 150.01150103	Serial No.: 10/771,043
	Applicant(s): Gurtej S. Sandhu	Confirmation No.: Unassigned
	Application Filing Date: February 3, 2004	Group: Unassigned
	Information Disclosure Statement mailed: April 29, 2004	

	2-293644	12/04/90	Japan (w/abstract)				X
	386,660	09/12/90	EP (w/abstract)				X
	3-48748	03/01/91	Japan (w/abstract)				X
	60-210752	10/85	Japan (w/abstract)				X
	2-69658	03/90	Japan				X

OTHER DOCUMENTS (Including Authors, Title, Date, Pertinent Papers, etc.)

Examiner Initial	Copy Enclosed	Document Description
Y		Aizenshtein et al., "Method of measurement of the rate of deposition of pure metals from the gas phase," <i>Chem. Abstr.</i> , 1966; 64: abstract 1747e.
		Aizenshtein et al., "Method of Measuring Rate of Pure Metals Deposition from the gas phase," <i>Tsvetnye Metally The Soviet Journal of Non-Ferrous Metals</i> , 6(9): 72-74.
		Bardin et al., "Voltametry of Ruthenate, Determination of Ruthenium from the Electrochemical Reduction of Ruthenium," <i>Journal of Analytical Chemistry of the USSR</i> , 1975;30: 642-645.
		Bates, J.R. et al., "The influence of the electrodeposition parameters on the morphology of organo-transition metal complexes for thin film gas sensor application", <i>Thin Solid Films</i> , 1997;299: 18-24.
		Brown et al., "New method for the characterization of domain morphology of polymer blends using ruthenium tetroxide staining and low voltage scanning electron microscopy (LVSEM)," <i>Polymer</i> , 1997; 38(15): 3937-3945.
		Kawahara et al., "(Ba,Sr)TiO ₃ Films Prepared by Liquid Source Chemical Vapor Deposition on Ru Electrodes," <i>Jpn Journ Appl Phys</i> , 1996;35 (Part 1, No. 9B): 4880-4885.
		Kawahara et al., "(Ba, Sr)TiO ₃ Films Prepared by Liquid Source Chemical Vapor Deposition on Ru Electrodes," <i>J. Appl. Phys.</i> , 1996;35: 4880-4885.
✓		Koda et al., "Radioactivation determination of ruthenium," <i>Chem Abstr</i> , 1979;90: abstract 114382q.

EXAMINER Helew Gah	Date Considered 12/15/03 Printed 05/26/03
*Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP 607. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	

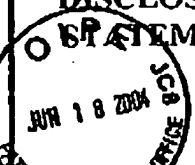
PAGE 57 * RCVD AT 4/29/2004 4:18:51 PM [Eastern Daylight Time] * SVR:USPTO-EFXRF-4/3 * DNIS:8729306 * CSID:1 612 305 1228 * DURATION (mm:ss):03:16

PAGE 8/9 * RCVD AT 12/9/2004 1:50:37 PM [Eastern Standard Time] * SVR:USPTO-EFXRF-1/0 * DNIS:8729306 * CSID:6123051228 * DURATION (mm:ss):02:50

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INFORMATION DISCLOSURE STATEMENT 	Atty. Docket No.: 150.01150103	Serial No.: 10/771,043
	Applicant(s): Gurtej S. Sandhu	Confirmation No.: 1538
	Application Filing Date: February 3, 2004	Group: 1743
	Information Disclosure Statement mailed: June 16, 2004	

U.S. PATENT DOCUMENTS

Examiner Initial	Copy Enclosed	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
		5,653,807	08/05/97	Crumbaker			

FOREIGN PATENT DOCUMENTS

Examiner Initial	Copy Enclosed	Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
Y6	X	1,576,658	08/01/69	France (w/abstract)			X	
Y6	X	2-293644	12/04/90	Japan (w/abstract)			X	
Y6	X	3-48748	03/01/91	Japan (w/abstract)			X	
Y6	X	2-69658	03/08/90	Japan (w/abstract)				X

OTHER DOCUMENTS (Including Authors, Title, Date, Pertinent Papers, etc.)

Examiner Initial	Copy Enclosed	Document Description
Y6	X	Akinfiyeva, T.A., "Basis for the maximum allowable concentration of ruthenium dioxide in the air of work areas," <i>Gigiena Truda i Professional'nye Zabolevaniya</i> , 1981:46-47 (English Abstract Included)
	X	Crawford et al., "Use of the Hazop Analysis for Evaluation of CVD reactors," <i>Journal de Physique IV</i> , September 1991: C2-459- C2-466.
	X	Gale et al., "Interaction of Safety and the facility for Photovoltaic R & D," <i>American Institute of Physics Conference Proceedings</i> , 1988;66:145-151
	X	Koda et al., "Radioactivation determination of ruthenium," <i>Kyoto Daigaku Genshiro Jikkensho Gakujutsu Koenkai Koen Yoshishyu</i> , 1976;10:25-27. (English Translation)
	X	Lu et al., "Epitaxial growth of RuO ₂ thin films by metal-organic chemical vapor deposition," <i>Thin Solid Films</i> , 1999;340:140-144.
	X	Orlow et al., "Detection of Ruthenium in Platinum Alloys," <i>Chemiker-Zeitung</i> , 1908;32:77. (English Translation)

EXAMINER <i>Yelue Hal</i>	Date Considered <i>08/06/04</i>
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